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CONTENTS

ARTICLES

- Enhancement of Light Trapping for Thin Film Solar Cells** 743
Yasha Yi, Wei Guo, and Yueheng Peng
- Fabrication of $\text{Si}_{1-x}\text{Ge}_x$ layer on Si Substrate by Screen-printing** 749
Masahiro Nakahara, Moeko Matsubara,
Shota Suzuki, Shogo Fukami,
Marwan Dhamrin, and Noritaka Usami
- Modelling of III-nitride Epitaxial Layers Grown on Silicon
Substrates with Low Dislocation-densities** 755
Khaled H. Khafagy, Tarek M. Hatem,
and Salah M. Bedair
- Material Removal Simulation in Sawing Processes of Photovoltaic
Silicon** 761
F. Wallburg, M. Kuna, and S. Schoenfelder
- Effects of Surface Doping of Si Absorbers on the Band Alignment
and Electrical Performance of TiO_2 -based Electron-selective
Contacts** 769
Hyunju Lee, Takefumi Kamioka,
Noritaka Usami, and Yoshio Ohshita
- Study of MnO_2 -graphene Oxide Nanocomposites for Supercapacitor
Applications** 777
Rahul Singhal, Justin Fagnoni, David Thorne,
Peter K. LeMaire, Xavier Martinez, Chen Zhao,
Ram K. Gupta, David Uhl, Ellen Scanley,
Christine C. Broadbridge, Mani Manivannan,
and Rishikesh Pandey
- Oxygen Anion Diffusion in Doped Ceria $\text{M}_x\text{Ce}_{1-x}\text{O}_{2-0.5x}$ (M=Gd,
Sm and Pr): A Molecular Dynamics Simulation Study.** 783
Neetu Kumari, Uzma Anjum, M. Ali Haider,
and Suddhastawa Basu